

Application No. 10/705,783 – LOF et al.
Atty Dkt. No. 081468-0306524
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Consideration of each listed application is earnestly solicited since unpublished patent applications are contemplated as IDS material; see the exception in Rule 98(a)(2)(iii) and note the penultimate sentence of MPEP 609.

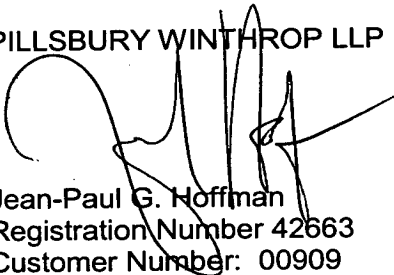
Further, in keeping with MPEP 609, subsec. C(2), 2nd para., line 10 to end of the paragraph (especially note lines 18-25) **PLEASE RETURN A COPY OF THIS LETTER** with the Examiner's initials adjacent each above listing so that applicant will know that each listed application has been considered as required by PTO policy.

Secondly, please consider each document which is listed on the attached Form PTO-1449 and return a copy of that form with the Examiner's initials adjacent each citation, a copy of each document enclosed except for any U.S. patents and published patent applications. It is respectfully requested that these documents listed on the Form PTO-1449 be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

Respectfully Submitted,

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Atty.
Dkt. No.

M#

Client Ref.

306524

P-0381.020-US

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: LOF et al.

Appln. No.: 10/705,783

Filing Date: November 12, 2003

Date: June 22, 2004

Page 1 of 1

Examiner:

Group Art Unit: 1756

U.S. PATENT DOCUMENTS

| Examiner's Initials* | Document Number | Date MM/YYYY | Name (Family Name of First Inventor) | Class | Sub Class | Filing Date (if appropriate) |
|-------------------------|--------------------|-----------------|-----------------------------------------|-------------|--------------|------------------------------------|
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FOREIGN PATENT DOCUMENTS

| | Document Number | Date MM/YYYY | Country | Inventor Name | English Abstract | | Translation Readily Available | |
|--|--------------------|-----------------|---------|---------------|---------------------|----|-------------------------------------|----|
| | | | | | Enclosed | No | Enclose | No |
| | LR | WO 03/077037 | 09/2003 | PCT | ROSTALSKI | | | |
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OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

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|-----|------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|--|--|--|
| UR | B. LIN, "The k_3 coefficient in nonparaxial λ/NA scaling equations for resolution, depth of focus, and immersion lithography, <i>J. Microlith., Microfab., Microsyst.</i> 1(1):7-12 (2002) | | | |
| VR | | | | |
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| ZR | | | | |
| AAR | | | | |
| BBR | | | | |
| CCR | | | | |

Examiner

Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.